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## Linde expands for sub 10nm geometries

Gases and engineering company The Linde Group (Booth #5644 in the North hall) is investing in expansion of existing products to improve business continuity planning while adding new products with improved purity to meet the growing needs of sub-10nm semiconductor factories and advanced flat panel manufacturers. Linde remains the global leader in rare gas and laser mixture production technology.

Linde has expanded capacity for fluorine/nitrogen mixtures at Medford, Oregon for etching and chamber cleaning applications.

- This allows both low- and high-pressure fluorine and nitrogen mixture production.
- On-site high-purity fluorine production minimizes third-party supply issues.
- The product line is expanding to include fluorine/argon mixtures in place with tri-mix capability (fluorine/argon/nitrogen) later in 2018.
- This facility complements fluorine mixture production at the Linde Alpha, New Jersey facility.

Linde is also developing deposition precursors and etch gases: silicon precursors, digermanium mixtures, high K and metal gate precursors, isotope gases and etch gases such as CF<sub>3</sub>I (trifluoriodomethane) and custom fluorinated silane.

"Linde's story this year is continued investment for customers," said Paul Stockman, Linde Electronics' Head of Market Development. "What we're doing in the US mirrors what we're doing globally, which is investing in new materials and new production capabilities and locating them close to where our customers are. We have uniform processes and multiple sites of production, and looking to optimize supply chains for our customers."

"Linde recognizes that our customers continue to make investments in new processes and technologies. We are committed to investing with them for the materials they will require now and in the future", states Matt Adams, Head of Sales and Marketing for Linde Electronics and Specialty Products.

